

INFORMATION DISCLOSURE
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APPLICATION



(PTO-1449)

ATTY. DOCKET NO.
6217/Consilium/DV

SERIAL NO.
09/927,444

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APPLICANT
Nicholas A. WARD et al.

FILING DATE
August 13, 2001

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2812

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	4,796,194	01/03/89	Atherton			08/20/86
	5,089,970	02/18/92	Lee et al.			10/05/89
	5,108,570	04/28/92	Wang			03/30/90
	5,220,517	06/15/93	Sierk et al.			08/31/90
	5,236,868	08/17/93	Nulman			04/20/90
	5,260,868	11/09/93	Gupta et al.			10/15/91
	5,295,242	03/15/94	Mashruwala et al.			11/02/90
	5,309,221	05/03/94	Fischer et al.			12/31/91
	5,329,463	07/12/94	Sierk et al.			01/13/93
	5,367,624	11/22/94	Cooper			06/11/93
	5,398,336	03/14/95	Tantry et al.			06/16/93
	5,402,367	03/28/95	Sullivan et al.			07/19/93
	5,408,405	04/18/95	Mozumder et al.			09/20/93
	5,410,473	04/25/95	Kaneko et al.			12/16/92

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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	01-283934	11/15/89	Japan			X	
	2,050,247	08/29/91	Canada			X	

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Dishon, G., D. Eylon, M. Finarov, and A. Shulman. "Dielectric CMP Advanced Process Control Based on Integrated Monitoring." Ltd. Rehoveth, Israel: Nova Measuring Instruments.

Runyan, W. R., and K. E. Bean. 1990. "Semiconductor Integrated Circuit Processing Technology." pg. 48. Reading, Massachusetts: Addison-Wesley Publishing Company.

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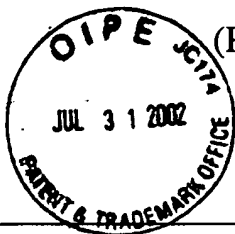
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1/9/04

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	5,490,097	02/06/96	Swenson et al.			08/06/93
	5,495,417	02/27/96	Fuduka et al.			03/16/93
	5,497,316	03/05/96	Sierk et al.			04/04/95
	5,503,707	04/02/96	Maung et al.			09/22/93
	5,508,947	04/16/96	Sierk et al.			05/13/94
	5,629,216	05/13/97	Wijaranakula et al.			02/27/96
	5,657,254	08/12/97	Sierk et al.			04/15/96
	5,661,669	08/26/97	Mozumder et al.			06/07/95
	5,694,325	12/02/97	Eukuda et al.			11/22/95
	5,698,989	12/16/97	Nulman			09/13/96
	5,719,495	02/17/98	Mostchi			06/05/96
	5,740,429	04/14/98	Wang et al.			07/07/95
	5,751,582	05/12/98	Saxena et al.			09/24/96
	5,754,297	05/19/98	Nulman			04/14/97
	5,764,543	06/09/98	Kennedy			06/16/95

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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	2,165,847	08/29/91	Canada			X	
	2,194,855	08/29/91	Canada			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	Zorich, Robert. 1991. <i>Handbook of Quality Integrated Circuit Manufacturing</i> . pp. 464-498 San Diego, California: Academic Press, Inc.		
	Rampalli, Prasad, Arakere Ramesh, and Nimish Shah. 1991. <i>CEPT—A Computer-Aided Manufacturing Application for Managing Equipment Reliability and Availability in the Semiconductor Industry</i>. New York, New York: IEEE.		
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	5,808,303	09/15/98	Schlagheck et al.			01/29/97
	5,838,595	11/17/98	Sullivan et al.			11/25/96
	5,883,437	03/16/99	Maruyama et al.			12/28/95
	5,910,011	06/08/99	Cruse			05/12/97
	6,054,379	04/25/00	Yau et al.			02/11/98

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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	05-151231	06/18/93	Japan				X
	05-216896	08/27/93	Japan				X
	05-266029	10/15/93	Japan				X
	06-110894	04/22/94	Japan				X
	06-176994	06/24/94	Japan				X
	06-252236	09/09/94	Japan				X
	06-260380	09/16/94	Japan				X
	08-149583	06/07/96	Japan			X	
	09-34535	02/07/97	Japan			X	
	EP 0877308 A2	11/11/98	Europe			X	
	11-67853	03/09/99	Japan			X	
	1072967A3	11/21/01	Europe			X	

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	Moyne, James R., Nauman Chaudhry, and Roland Telfeyan. 1995. "Adaptive Extensions to a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology</i> . Ann Arbor, Michigan: University of Michigan Display Technology Manufacturing Center.
	Moyne, James, Roland Telfeyan, Arnon Hurwitz, and John Taylor. August 1995. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Advanced Semiconductor Manufacturing Conference and Workshop</i> . Ann Arbor, Michigan: The University of Michigan, Electrical Engineering & Computer Science Center for Display Technology & Manufacturing.
EXAMINER	DATE CONSIDERED 1/9/04

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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT APPLICATION NO.	FILING DATE	NAME	TITLE	CLASS	SUB- CLASS
	09/363,966	07/29/99	Arackaparambil et al.	Computer Integrated Manufacturing Techniques		
	09/469,227	12/22/99	Somekh et al.	Multi-Tool Control System, Method and Medium		
	09/619,044	07/19/00	Yuan	System and Method of Exporting or Importing Object Data in a Manufacturing Execution System		
	09/637,620	08/11/00	Chi et al.	Generic Interface Builder		
	09/656,031	09/06/00	Chi et al.	Dispatching Component for Associating Manufacturing Facility Service Requestors with Service Providers		

FOREIGN PATENT DOCUMENTS

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						Yes	No

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	Zhou, Zhen-Hong and Rafael Reif. August 1995. "Epi-Film Thickness Measurements Using Emission Fourier Transform Infrared Spectroscopy—Part II: Real-Time <i>in Situ</i> Process Monitoring and Control." IEEE Transactions on Semiconductor Manufacturing, Vol. 8, No. 3.
	Telfeyan, Roland, James Moyne, Nauman Chaudhry, James Pugmire, Scott Shellman, Duane Boning, William Moyne, Arnon Hurwitz, and John Taylor. October 1995. "A Multi-Level Approach to the Control of a Chemical-Mechanical Planarization Process." Minneapolis, Minnesota: 42 nd National Symposium of the American Vacuum Society.
	Chang, E., B. Stine, T. Maung, R. Divecha, D. Boning, J. Chung, K. Chang, G. Ray, D. Bradbury, O. S. Nakagawa, S. Oh, and D. Bartelink. December 1995. "Using a Statistical Metrology Framework to Identify Systematic and Random Sources of Die- and Wafer-level ILD Thickness Variation in CMP Processes." Washington, D.C.: International Electron Devices Meeting.

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EXAMINER'S INITIALS	PATENT APPLICATION NO.	FILING DATE	NAME	TITLE	CLASS	SUB- CLASS
	09/655,542	09/06/00	Yuan	System, Method and Medium for Defining Palettes to Transform an Application Program Interface for a Service		
	09/725,908	11/30/00	Chi et al.	Dynamic Subject Information Generation in Message Services of Distributed Object Systems		
	09/800,980	03/08/01	Hawkins et al.	Dynamic and Extensible Task Guide		
	09/811,667	03/20/01	Yuan et al.	Fault Tolerant and Automated Computer Software Workflow		

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						Yes	No

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	Dishon, G., M. Finarov, R. Kipper, J.W. Curry, T. Schraub, D. Trojan, 4 th Stambaugh, Y. Li and J. Ben-Jacob. February 1996. "On-Line Integrated Metrology for CMP Processing." Santa Clara, California: VMIC Speciality Conferences, 1 st International CMP Planarization Conference.
	Smith, Taber, Duane Boning, James Moyne, Arnon Hurwitz, and John Curry. June 1996. "Compensating for CMP Pad Wear Using Run by Run Feedback Control." Santa Clara, California: VLSI Multilevel Interconnect Conference.
	Boning, Duane, William Moyne, Taber Smith, James Moyne, Roland Telfeyan, Arnon Hurwitz, Scott Shellman, and John Taylor. October 1996. "Run by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans. CPMT (C)</i> , Vol. 19, No. 4, pp. 307-314.
	SEMI. [1986] 1996. "Standard for Definition and Measurement of Equipment Reliability, Availability, and Maintainability (RAM)." SEMI E10-96.

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						Yes No

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	Van Zant, Peter. 1997. <i>Microchip Fabrication: A Practical Guide to Semiconductor Processing</i> . Third Edition, pp. 472-478. New York, New York: McGraw-Hill.
	Campbell, W. Jarrett, and Anthony J. Toprac. February 11-12, 1998. "Run-to-Run Control in Microelectronics Manufacturing." Advanced Micro Devices, TWMCC.
	Edgar, Thomas F., Stephanie W. Butler, Jarrett Campbell, Carlos Pfeiffer, Chris Bode, Sung Bo Hwang, and K.S. Balakrishnan. May 1998. "Automatic Control in Microelectronics Manufacturing: Practices, Challenges, and Possibilities." Automatica, Vol. 36, pp. 1567-1603, 2000.
	Moyne, James, and John Curry. June 1998. "A Fully Automated Chemical-Mechanical Planarization Process." Santa Clara, California: VLSI Multilevel Interconnection (V-MIC) Conference.
	SEMI. July 1998. <i>New Standard: Provisional Specification for CIM Framework Domain Architecture</i> . Mountain View, California: SEMI Standards. SEMI Draft Doc. 2817.
	Consilium. August 1998. <i>Quality Management Component: QMC™ and QMC-Link™ Overview</i> . Mountain View, California: Consilium, Inc.
	Chemali, Chadi El, James Moyne, Kareemullah Khan, Rock Nadeau, Paul Smith, John Colt, Jonathan Chapple-Sokol, and Tarun Parikh. November 1998. "Multizone Uniformity Control of a CMP Process Utilizing a Pre and Post-Measurement Strategy." Seattle, Washington: SEMETECH Symposium.
	Consilium. 1998. <i>FAB300™</i> . Mountain View, California: Consilium, Inc.
	Khan, Kareemullah, Victor Solakhain, Anthony Ricci, Tier Gu, and James Moyne. 1998. "Run-to-Run Control of ITO Deposition Process." Ann Arbor, Michigan.

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						Yes	No

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	Consilium. January 1999. "FAB300™: Consilium's Next Generation MES Solution of Software and Services which Control and Automate Real-Time FAB Operations." www.consilium.com/products/fab300_page.htm#FAB300 Introduction
	Consilium. July 1999. "Increasing Overall Equipment Effectiveness (OEE) in Fab Manufacturing by Implementing Consilium's Next-Generation Manufacturing Execution System - MES II." Semiconductor Fabtech Edition 10.
	Consilium Corporate Brochure. October 1999. www.consilium.com
	Moyne, James. October 1999. "Advancements in CMP Process Automation and Control." Hawaii: (Invited paper and presentation to) Third International Symposium on Chemical Mechanical Polishing in IC Device Manufacturing: 196 th Meeting of the Electrochemical Society.
	Consilium. November 1999. <i>FAB300™ Update</i> .
	SEMI. 2000. "Provisional Specification for CIM Framework Scheduling Component." San Jose, California. SEMI E105-1000.
	Lee, Brian, Duane S. Boning, Winthrop Baylies, Noel Poduje, Pat Hester, Yong Xia, John Valley, Chris Koliopoulus, Dale Hetherington, Hong Jiang Sun, and Michael Lacy. April 2001. "Wafer Nanotopography Effects on CMP: Experimental Validation of Modeling Methods." San Francisco, California: Materials Research Society Spring Meeting.
	NovaScan 2020. February 2002. "Superior Integrated Process Control for Emerging CMP High-End Applications."
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INFORMATION DISCLOSURE CITATION IN AN APPLICATION <div style="display: flex; justify-content: space-around; align-items: center;"> <div style="text-align: center;">  </div> <div style="text-align: center;">  </div> </div>				ATTY. DOCKET NO. 6217/Consilium/DV		SERIAL NO. 09/927,444	
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_____	4,698,766	10/06/87	Entwistle et al.			05/17/85
_____	4,967,381	10/30/90	Lane et al.			07/06/89
_____	5,208,765	05/04/93	Turnbull			07/20/90
_____	5,226,118	07/06/93	Baker et al.			01/29/91
_____	5,231,585	07/27/93	Kobayashi et al.			06/20/90
_____	5,420,796	05/30/95	Weling et al.			12/23/93
_____	5,469,361	11/21/95	Moyne			06/06/94
_____	5,525,808	06/11/96	Irie et al.			12/20/94
_____	5,586,039	12/17/96	Hirsch et al.			02/27/95
_____	5,603,707	02/18/97	Trombetta et al.			11/28/95
_____	5,664,987	09/09/97	Renteln			09/04/96
_____	5,812,407	09/22/98	Sato et al.			08/12/97
_____	5,828,778	10/27/98	Hagi et al.			06/12/96
_____	5,832,224	11/03/98	Fehskens et al.			06/14/96

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						Yes No
_____	61-171147	08/01/86	Japan			_____ X
_____	6-184434	07/05/94	Japan			_____ X
_____	0 621 522 A2	10/26/94	Europe			X _____
_____	8 50161	02/20/96	Japan			_____ X
_____	8-304023	11/22/96	Japan			_____ X

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_____	February 1984. "Method and Apparatus of in Situ Measurement and Overlay Error Analysis for Correcting Step and Repeat Lithographic Cameras." IBM Technical Disclosure Bulletin, pp. 4855-4859.
_____	October 1984. "Method to Characterize the Stability of a Step and Repeat Lithographic System." IBM Technical Disclosure Bulletin, pp. 2857-2860.

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	5,839,964	01/12/99	Wang et al.			10/25/96
	5,863,807	01/26/99	Iang et al.			03/15/96
	5,870,306	02/09/99	Harada			06/13/97
	5,903,455	05/11/99	Sharpe, Jr. et al.			12/12/96
	5,916,016	06/29/99	Bothra			10/23/97
<i>ex</i>	5,923,553	07/13/99	Yi			10/05/96
	5,930,138	07/27/99	Lin et al.			09/10/97
	5,940,300	08/17/99	Ozaki			05/08/97
	5,960,214	09/28/99	Sharpe, Jr. et al.			12/04/96
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	6,078,845	06/20/00	Friedman			11/25/96
	6,112,130	08/29/00	Fukuda et al.			10/01/97
	6,148,246	11/14/00	Kawazome			06/10/98

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						Yes	No
	0 747 795 A2	12/11/96	Europe			X	
	10-173029	06/26/98	Japan				X
	0 895 145 A1	02/03/99	Europe			X	
	11 126816	05/11/99	Japan				X

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Schmid, Hans Albrecht. 1995. "Creating the Architecture of a Manufacturing Framework by Design Patterns." Austin, Texas: OOPSLA.
Baliga, John. July 1999. "Advanced Process Control: Soon to be a Must." Cahners Semiconductor International. www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp

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_____	6,175,777	01/16/01	Kim			01/16/98
_____	6,178,390	01/23/01	Jun			09/08/98
_____	6,185,324	02/06/01	Ishihara et al			01/31/95
_____	6,192,291	02/20/01	Kwon			10/08/98
_____	6,197,604	03/06/01	Miller et al.			10/01/98
_____	6,211,094	04/03/01	Iun et al			08/23/99
_____	6,226,792	05/01/01	Goiffon et al.			10/14/98
_____	6,230,069	05/08/01	Campbell et al.			06/26/98
_____	6,236,903	05/22/01	Kim et al.			09/25/98
_____	6,240,330	05/29/01	Kurtzberg et al.			05/28/97

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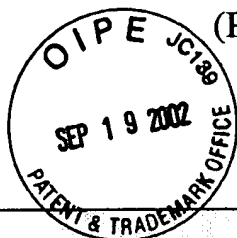
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
_____	11,135,601	05/21/99	Japan				X
_____	WO 00/05759	02/03/00	WO			X	
_____	WO 00/35063	06/15/00	WO			X	

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_____	July 5, 2001. "Motorola and Advanced Micro Devices Buy ObjectSpace Catalyst Advanced Process Control Product for Five Wafer Fabs." Semiconductor FABTECH. www.semiconductorfabtech.com/industry.news/9907/20.07.shtml
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_____	Johnson, Bob. June 10, 2002. "Advanced Process Control Key to Moore's Law." Gartner, Inc.
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	6,240,331	05/29/01	Yun			08/18/98
	6,248,602	06/19/01	Bode et al.			11/01/99
	6,252,412	06/26/01	Talbot et al.			01/08/99
	6,263,255	07/17/01	Tan et al.			05/18/98
	6,292,708	09/18/01	Allen et al.			06/11/98
	6,298,274	10/02/01	Inoue			09/01/99
<i>W</i>	6,303,395	10/16/01	Nulman			06/01/99
	6,345,315	02/05/02	Mishra			08/12/98
	6,366,934	04/02/02	Cheng et al.			06/02/99

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	WO 00/79355 A1	12/28/00	WO			X	
	2001-76982	03/23/01	Japan				X
	WO 01/33501 A1	05/10/01	WO			X	

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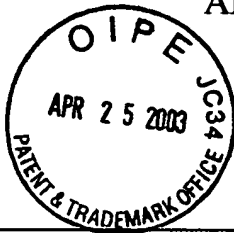
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_____	3,229,198	01/11/66	Libby			09/28/62
_____	4,000,458	12/28/76	Miller et al.			08/21/75
_____	4,302,721	11/24/81	Urbanek et al.			05/15/79
_____	4,750,141	06/07/88	Judell et al.			11/26/85
_____	4,757,259	07/12/88	Charpentier			11/05/86
_____	4,938,600	07/03/90	Into			02/09/89
_____	5,283,141	02/01/94	Yoon et al.			03/05/92
_____	5,338,630	08/16/94	Yoon et al.			11/18/93
_____	5,485,082	01/16/96	Wisspeintner et al.			04/05/90
_____	5,497,381	03/05/96	O'Donoghue et al.			06/01/95
_____	5,511,005	04/23/96	Abbe et al.			02/16/94
_____	5,519,605	05/21/96	Cawfield			10/24/94
_____	5,526,293	06/11/96	Mozumder et al.			12/17/93
_____	5,541,510	06/30/96	Dantelson			04/06/95
_____	5,546,312	08/13/96	Mozumder et al.			02/24/94
_____	5,553,195	09/03/96	Meijer			09/29/94
_____	5,602,492	02/11/97	Cresswell et al.			04/28/94
_____	5,617,023	04/01/97	Skalski			02/02/95
_____	5,627,083	05/06/97	Tounai			05/12/95
_____	5,642,296	06/24/97	Saxena			07/29/93
_____	5,646,870	07/08/97	Krivokapic et al.			02/13/95
_____	5,649,169	07/15/97	Berezin et al.			06/20/95
_____	5,654,903	08/05/97	Reitman et al.			11/07/95
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	5,674,787	10/07/97	Zhao et al.			01/16/96
	5,719,796	02/17/98	Chen			12/04/95
	5,735,055	04/07/98	Hochbein et al.			04/23/96
	5,761,064	06/02/98	La et al.			10/06/95
	5,777,901	07/07/98	Berezin et al.			09/29/95
	5,787,021	07/28/98	Samaha			12/18/95
	5,787,269	07/28/98	Hyodo			09/19/95
	5,825,913	10/20/98	Rostami et al.			07/18/95
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	5,910,846	06/08/99	Sandhu			08/19/97
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	5,960,185	09/28/99	Nguyen			06/24/96
	5,961,369	10/05/99	Bartels et al.			06/04/98
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	6,017,771	01/25/00	Yang et al.			04/27/98
	6,036,349	03/14/00	Gombar			07/26/96
	6,064,759	05/16/00	Buckley et al.			11/06/97
	6,072,313	06/06/00	Li et al.			06/17/97
	6,097,887	08/01/00	Hardikar et al.			10/27/97
	6,108,092	08/22/00	Sandhu			06/08/99
	6,127,263	10/03/00	Parikh			07/10/98
<i>SM</i>	6,136,163	10/24/00	Cheung et al.			03/05/99
	6,141,660	10/31/00	Bach et al.			07/16/98
	6,143,646	11/07/00	Wetzel			06/03/97
	6,148,099	11/14/00	Lee et al.			07/03/97
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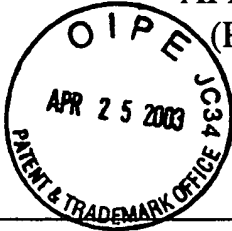
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	6,159,644	12/12/00	Sato et al.			03/06/96
<i>82</i>	6,161,054	12/12/00	Rosenthal et al.			09/17/98
	6,169,931	01/02/01	Runnels			06/29/98
	6,172,756	01/09/01	Chalmers et al.			12/11/98
	6,173,240	01/09/01	Sepulveda et al.			11/02/98
	6,191,864	02/20/01	Sandhu			02/29/00
	6,204,165	03/20/01	Ghoshal			06/24/99
	6,210,983	04/03/01	Atchison et al.			06/15/99
	6,214,734	04/10/01	Bothra et al.			11/20/98
	6,217,412	04/17/01	Campbell et al.			08/11/99
	6,222,936	04/24/01	Phan et al.			09/13/99
	2001/0001755	05/24/01	Sandhu et al.			12/29/00
	2001/0003084	06/07/01	Finarov			12/04/00
	6,246,972	06/12/01	Klimasauskas			05/27/99
	6,276,989	08/21/01	Campbell et al.			08/11/99
	6,280,289	08/28/01	Wiswesser et al.			11/02/98
	6,284,622	09/04/01	Campbell et al.			10/25/99
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	6,304,999	10/16/01	Toprac et al.			10/23/00
	2001/0030366	10/18/01	Nakano et al.			03/07/01
	6,307,628	10/23/01	Lu et al.			08/18/00
	6,314,379	11/06/01	Hu et al.			12/04/97
	2001/0039462	11/08/01	Mendez et al.			04/02/01
	6,320,655	11/20/01	Matsushita et al.			03/15/00

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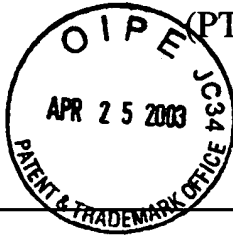
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_____	2002/0149359	10/17/02	Crouzen et al.	_____	_____	08/18/01
_____	6,479,902	11/12/02	Lopatin et al.	_____	_____	06/29/00
_____	6,479,990	11/12/02	Mednikov et al.	_____	_____	06/18/01
_____	2002/0185658	12/12/02	Inoue et al.	_____	_____	06/14/01
_____	2002/0193902	12/19/02	Shanmugasundram et al.	_____	_____	06/18/02
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_____	2002/0197934	12/26/02	Paik	_____	_____	11/30/01
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_____	6,503,839	01/07/03	Gonzales et al.	_____	_____	07/03/01
_____	2003/0020909	01/30/03	Adams et al.	_____	_____	04/09/01
_____	2003/0020928	01/30/03	Ritzdorf et al.	_____	_____	07/09/01
_____	6,517,413	02/11/03	Hu et al.	_____	_____	10/25/00

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_____	61-66104	04/04/86	Japan	_____	_____	X	_____
_____	3-202710	09/04/91	Japan	_____	_____	X	_____
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_____	9-246547	09/19/97	Japan	_____	_____	X	_____
_____	WO 98/05066	02/05/98	WIPO	_____	_____	X	_____
_____	10-34522	02/10/98	Japan	_____	_____	X	_____
_____	0-869-652	10/07/98	Europe	_____	_____	X	_____
_____	WO 99/09371	02/25/99	WIPO	_____	_____	X	_____
_____	0-910-123	04/21/99	Europe	_____	_____	X	_____
_____	0-932-194	07/28/99	Europe	_____	_____	X	_____
_____	WO 00/00874	01/06/00	WIPO	_____	_____	X	_____
_____	2000-183001	06/30/00	Japan	_____	_____	X	_____

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—	1 071 128	01/24/01	Europe			X	
—	WO 01/18623	03/15/01	WIPO			X	
—	WO 01/25865	04/12/01	WIPO			X	
—	434103	05/16/01	Taiwan			X	
—	436383	05/28/01	Taiwan			X	
—	455938	09/21/01	Taiwan			X	
—	455976	09/21/01	Taiwan			X	
—	2001-284299	10/12/01	Japan			X	
—	2001-305108	10/31/01	Japan			X	
—	2002-9030	01/11/02	Japan			X	
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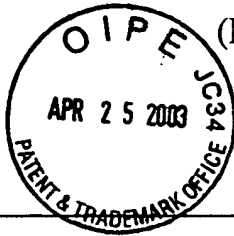
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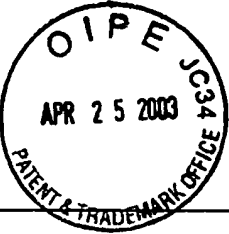

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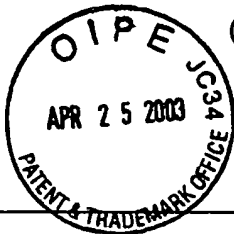
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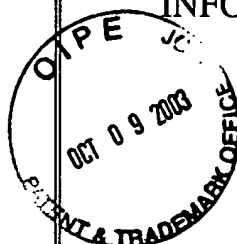
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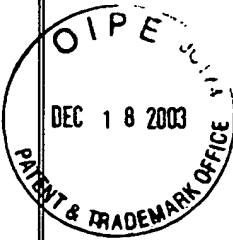
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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
_____	3,767,900	10/23/73	Chao et al.	_____	_____	06/23/71
_____	3,920,965	11/18/75	Sohrwardy	_____	_____	03/04/74
_____	4,368,510	01/11/83	Anderson	_____	_____	10/20/80
_____	4,616,308	10/07/86	Morshedi et al.	_____	_____	12/02/85
_____	4,663,703	05/05/87	Axelby et al.	_____	_____	10/02/85
_____	5,347,446	09/13/94	Iino et al.	_____	_____	02/10/92
_____	5,519,605	05/21/96	Cawfield	_____	_____	10/24/94
_____	6,128,016	10/03/00	Coelho et al.	_____	_____	12/20/96
_____	6,219,711	04/17/01	Chari	_____	_____	10/01/97
_____	6,249,712	06/19/01	Boiquaye	_____	_____	09/25/96
_____	6,278,899	08/21/01	Piche et al.	_____	_____	10/06/98
_____	2001/0039462	11/08/01	Mendez et al.	_____	_____	04/02/01
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_____	2002/0128805	09/12/02	Goldman et al.	_____	_____	12/26/00
_____	_____	_____	_____	_____	_____	_____

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
_____	EP 1 067 757	01/10/01	Europe	_____	_____	X	_____
_____	WO 01/33277	05/10/01	WO	_____	_____	X	_____
_____	WO 02/31613 A2	04/18/02	WO	_____	_____	X	_____
_____	WO 02/31613 A3	04/18/02	WO	_____	_____	X	_____
_____	_____	_____	_____	_____	_____	_____	_____

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_____	Levine, Martin D. 1985. <i>Vision in Man and Machine</i>. New York: McGraw-Hill, Inc. pp. ix-xii, 1-58.
_____	Pilu, Maurizio. September 2001. "Undoing Page Curl Distortion Using Applicable Surfaces." <i>IEEE International Conference on Image Processing</i>. Thessalonica, Greece.
_____	23 May 2003. Written Opinion for PCT/US01/24910.
EXAMINER	DATE CONSIDERED
	1/9/04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

#13

SHEET 1 OF 1



INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
006217
USA/Consilium/Consilium

SERIAL NO.
09/927,444

APPLICANT
Nicholas A. WARD et al.

FILING DATE
August 13, 2001

GROUP
2812

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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	5,655,951	08/12/97	Meikle et al.			09/29/95
	5,823,854	10/20/98	Chen			05/28/96
	5,859,975	01/12/99	Brewer et al.			08/09/96
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						Yes	No
	2,347,885 A	09/20/00	GB			X	
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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#14

SHEET 2 OF 2

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION
(PTO-1449)

ATTY. DOCKET NO.
006217
USA/Consilium/Consilium

SERIAL NO.
09/927,444

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APPLICANT
Nicholas A. WARD et al.

Technology Center 2100

FILING DATE
August 13, 2001

GROUP
2812

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	El Chemali, Chadi et al. July/August 2000. "Multizone uniformity control of a chemical mechanical polishing process utilizing a pre- and postmeasurement strategy." <i>J. Vac. Sci. Technol.</i> Volume 18, No. 4. pp. 1287 - 1296.
	March 5, 2001. "KLA-Tencor Introduces First Production-worthy Copper CMP In-situ Film Thickness and End-point Control System." http://www.kla-tencor.com/j/servlet/NewsItem?newsItemID=74 .
	2002. "Microsense II - 5810: Non-Contact Capacitance Gaging Module." www.adetech.com .
	08 August 2003. PCT International Search Report from PCT/US03/08513.
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